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Advanced Fabrication Technologies for Micro/Nano Optics and Photonics VI

**Georg von Freymann
Winston V. Schoenfeld
Raymond C. Rumpf
Editors**

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Contents

- ix Conference Committee
- xii Towards future systems with nano-optics contributions (Plenary Paper) [8616-101]
B. Kaminska, Simon Fraser Univ. (Canada) and NanoTech Security Corp. (Canada);
M. Najiminaini, Simon Fraser Univ. (Canada), Lawson Health Research Institute (Canada),
and The Univ. of Western Ontario (Canada); Y. Chuo, C. Landrock, B. Omrane, Simon
Fraser Univ. (Canada) and NanoTech Security Corp. (Canada); J. J. L. Carson, Lawson
Health Research Institute (Canada) and The Univ. of Western Ontario (Canada)
- xxvii MOEMS pressure sensors for geothermal well monitoring (Plenary Paper) [8616-102]
W. Challener, S. Palit, General Electric Global Research (United States); R. Jones, L. Airey,
R. Craddock, General Electric Measurement and Control (United Kingdom); A. Knobloch,
General Electric Global Research (United States)

SESSION 1 PLASMONIC STRUCTURES I

- 8613 02 **Precisely controlled plasmonic nanostructures and its application to nanolithography (Invited Paper) [8613-1]**
K. Ueno, Hokkaido Univ. (Japan) and Japan Science and Technology Agency (Japan);
H. Misawa, Hokkaido Univ. (Japan)
- 8613 04 **Chiral plasmonic nanostructures: experimental and numerical tools [8613-3]**
G. Gervinskas, Swinburne Univ. of Technology (Australia) and Melbourne Ctr. for
Nanofabrication (Australia); L. Rosa, Swinburne Univ. of Technology (Australia); E. Brasselet,
Lab. Ondes et Matière d'Aquitaine, CNRS, Univ. Bordeaux 1 (France); S. Juodkazis,
Swinburne Univ. of Technology (Australia) and Melbourne Ctr. for Nanofabrication
(Australia)
- 8613 05 **Nanoscale patterning of colloidal quantum dots for surface plasmon generation [8613-4]**
Y. Park, Y.-G. Roh, U. J. Kim, D.-Y. Chung, H. Suh, J. Kim, S. Cheon, J. Lee, T.-H. Kim,
K.-S. Cho, C.-W. Lee, Samsung Advanced Institute of Technology (Korea, Republic of)
- 8613 06 **Focused electron-beam induced deposition of plasmonic nanostructures from aqueous
solutions [8613-5]**
M. Bresin, N. Nehru, J. T. Hastings, Univ. of Kentucky (United States)

SESSION 2 NOVEL APPROACHES TO DIRECT LASER WRITING

- 8613 0A **Dynamic optical methods for direct laser written waveguides [8613-9]**
P. S. Salter, M. J. Booth, Univ. of Oxford (United Kingdom)

SESSION 3 PRECISE MATERIAL DEPOSITION

- 8613 0B **Tuning of optical properties by atomic layer deposition (Invited Paper) [8613-10]**
Y. Qin, Institute of Coal Chemistry (China); R. Vogelgesang, M. Eßlinger, Max-Planck-Institut für Festkörperforschung (Germany); M. Knez, CIC nanoGUNE Consolider (Spain) and Basque Foundation for Science (Spain)
- 8613 0C **Nonpolarizing single layer inorganic and double layer organic-inorganic one-dimensional guided mode resonance filters [8613-11]**
M. R. Saleem, The Univ. of Eastern Finland (Finland) and National Univ. of Sciences and Technology (Pakistan); S. Honkanen, J. Turunen, The Univ. of Eastern Finland (Finland)
- 8613 0D **III-V access waveguides using atomic layer deposition (Best Paper Award) [8613-12]**
K. Mnaymneh, Univ. of Michigan (United States); S. Frédérick, D. Dalacu, J. Lapointe, P. J. Poole, R. L. Williams, National Research Council Canada (Canada)
- 8613 0E **Wire grid polarizers fabricated by low angle deposition [8613-13]**
M. P. C. Watts, M. Little, E. Egan, A. Hochbaum, C. Johns, S. Stephansen, Agoura Technologies, Inc. (United States)

SESSION 4 3D STRUCTURES

- 8613 0I **Reversible microstructuring of lithium niobate by direct laser write technique [8613-17]**
V. Mizeikis, Shizuoka Univ. (Japan); D. Paipulas, V. Purlys, Vilnius Univ. (Lithuania); R. Buividas, S. Juodkazis, Swinburne Univ. of Technology (Australia)
- 8613 0J **Freeform mirror fabrication and metrology using a high performance test CGH and advanced alignment features [8613-18]**
S. Scheiding, M. Beier, U.-D. Zeitner, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany) and Friedrich-Schiller-Univ. Jena (Germany); S. Risse, A. Gebhardt, Fraunhofer-Institut für Angewandte Optik und Feinmechanik (Germany)
- 8613 0K **Flexible micro-optics fabrication by direct laser writing toward CMOS compatible 3D optical circuit [8613-19]**
C. Summitt, S. Wang, L. Johnson, M. Zaverton, T. Milster, Y. Takashima, College of Optical Sciences, The Univ. of Arizona (United States)

SESSION 5 PLASMONIC STRUCTURES II

- 8613 0M **Nanofabrication of surface-enhanced Raman scattering substrates for optical fiber sensors (Invited Paper) [8613-21]**
P. R. Stoddart, Swinburne Univ. of Technology (Australia); S. Jayawardhana, Univ. of Sri Jayewardenepura (Sri Lanka)
- 8613 0O **Holographic fabrication of nano-optical devices using single reflective optical element [8613-23]**
J. Lutkenhaus, D. George, D. Garrett, H. Zhang, Y. Lin, The Univ. of North Texas (United States)

SESSION 6 LARGE AREA STRUCTURING

- 8613 0R **P-Ink displays: flexible, low power, reflective color (Invited Paper)** [8613-26]
A. C. Arsenault, H. Wang, E. Henderson, F. Kerins, U. Kamp, L. Da Silva Bonifacio, P. H. Law, Opalux, Inc. (Canada); G. A. Ozin, Univ. of Toronto (Canada)
- 8613 0U **Microstructured optics for high performance optical systems** [8613-29]
A. Gatto, Carl Zeiss Jena GmbH (Germany)

SESSION 7 NOVEL APPLICATIONS AND MATERIALS FOR DLW

- 8613 0W **Photonic wire bonding: connecting nanophotonic circuits across chip boundaries (Invited Paper, MOEMS-MEMS Best Paper Award)** [8613-31]
C. Koos, J. Leuthold, W. Freude, N. Lindenmann, S. Koeber, G. Balthasar, J. Hoffmann, T. Hoose, P. Huebner, D. Hillerkuss, R. Schmogrow, Karlsruher Institut für Technologie (Germany)
- 8613 0X **Fundamental processes of refractive index modifications during femtosecond laser waveguide writing** [8613-32]
D. Schaefer, RWTH Aachen (Germany) and Fraunhofer-Institut für Lasertechnik (Germany); D. Schnitzler, Fraunhofer-Institut für Lasertechnik (Germany); I. Kelbassa, RWTH Aachen (Germany) and Fraunhofer-Institut für Lasertechnik (Germany)
- 8613 0Y **Two photon polymerization lithography for 3D microfabrication of single wall carbon nanotube/polymer composites** [8613-33]
S. Ushiba, S. Shoji, Osaka Univ. (Japan); P. Kuray, Rutgers, The State Univ. of New Jersey (United States); K. Masui, Osaka Univ. (Japan); J. Kono, Rice Univ. (United States); S. Kawata, Osaka Univ. (Japan)

SESSION 8 NANO- AND MICRO-OPTIC APPLICATIONS

- 8613 10 **Light sensitive waveguides fabricated by vacuum assisted microfluidics** [8613-35]
S. Baig, G. Jiang, M. R. Wang, Univ. of Miami (United States)
- 8613 12 **Flexible conductive polymer polarizer designed for a chemical tag** [8613-37]
C. M. Washburn, J. C. Jones, S. R. Vigil, P. S. Finnegan, R. R. Boye, J. D. Hunker, D. A. Scrymgeour, S. M. Dirk, B. G. Hance, J. M. Strong, L. M. Massey, M. T. Brumbach, Sandia National Labs. (United States)
- 8613 13 **Micro-optical grayscale excitation lenses for atom and ion trapping** [8613-38]
D. A. Scrymgeour, S. A. Kemme, R. R. Boye, A. R. Ellis, T. R. Carter, S. Samora, J. D. Hunker, Sandia National Labs. (United States)
- 8613 14 **A snapshot multispectral imager with integrated tiled filters and optical duplication** [8613-39]
B. Geelen, N. Tack, A. Lambrechts, IMEC (Belgium)

- 8613 15 **Micro-optical system as integration platform for III-N nanowire based opto-chemical detectors (Best Student Paper Award) [8613-40]**
R. Kleindienst, Technische Univ. Ilmenau (Germany); V. Cimalla, Fraunhofer-Institut für Angewandte Festkörperphysik (Germany); M. Eickhoff, Justus-Liebig-Univ. Giessen (Germany); A. Grewe, Technische Univ. Ilmenau (Germany); K. Holc, J. Schätzle, Fraunhofer-Institut für Angewandte Festkörperphysik (Germany); U. Schwarz, Fraunhofer-Institut für Angewandte Festkörperphysik (Germany) and Albert-Ludwigs-Univ. Freiburg (Germany); J. Teubert, Justus-Liebig-Univ. Giessen (Germany); S. Sinzinger, Technische Univ. Ilmenau (Germany)
- 8613 16 **Hyperspectral Fabry-Pérot filters for HgCdTe infrared detectors [8613-41]**
Y. Chang, Sivananthan Labs., Inc. (United States); C. H. Grein, Sivananthan Labs., Inc. (United States) and Univ. of Illinois at Chicago (United States); S. Velicu, M. Morley, EPIR Technologies, Inc. (United States); N. Gupta, U.S. Army Research Lab. (United States)

POSTER SESSION

- 8613 17 **Inkjet printed microlens array on patterned substrate [8613-42]**
P. Vilmi, R. Mylllä, T. Fabritius, The Univ. of Oulu (Finland)
- 8613 18 **Fabrication, replication, and characterization of microlenses for optofluidic applications [8613-43]**
L. Jonusauskas, A. Žukauskas, Vilnius Univ. (Lithuania); P. Danilevicius, Foundation for Research and Technology-Hellas (Greece); M. Malinauskas, Vilnius Univ. (Lithuania)
- 8613 19 **New fabrication method of glass packages with inclined optical windows for micromirrors on wafer level [8613-44]**
V. Stenichly, H.-J. Quenzer, U. Hofmann, J. Janes, B. Jensen, W. Benecke, Fraunhofer-Institut für Siliziumtechnologie (Germany)
- 8613 1A **Low-NA focused vortex beam lithography for below 100-nm feature size at 405 nm illumination [8613-45]**
M.-S. Kim, Ecole Polytechnique Fédérale de Lausanne (Switzerland) and SUSS MicroOptics SA (Switzerland); T. Scharf, H. P. Herzig, Ecole Polytechnique Fédérale de Lausanne (Switzerland); R. Voelkel, SUSS MicroOptics SA (Switzerland)
- 8613 1B **Light confinement effect of non-spherical nanoscale solid immersion lenses [8613-46]**
M.-S. Kim, Ecole Polytechnique Fédérale de Lausanne (Switzerland) and SUSS MicroOptics SA (Switzerland); T. Scharf, D. Nguyen, Ecole Polytechnique Fédérale de Lausanne (Switzerland); E. Keeler, S. Rydberg, W. Nakagawa, Montana State Univ. (United States); G. Osowecki, H. P. Herzig, Ecole Polytechnique Fédérale de Lausanne (Switzerland); R. Voelkel, SUSS MicroOptics SA (Switzerland)
- 8613 1C **Holographic fabrication of woodpile-type photonic crystal templates using silicon based single reflective optical element [8613-47]**
J. Lutkenhaus, D. George, K. Ohlinger, H. Zhang, The Univ. of North Texas (United States); Z. Poole, K. P. Chen, Univ. of Pittsburgh (United States); Y. Lin, The Univ. of North Texas (United States)

- 8613 1D **Advanced mask aligner lithography (AMALITH) [8613-48]**
L. A. Dunbar, G. Bergonzi, CSEM SA (Switzerland); U. Vogler, SUSS MicroOptics SA (Switzerland); S. Angeloni, CSEM SA (Switzerland); R. Kirner, A. Bramati, SUSS MicroOptics SA (Switzerland); B. Timotijevic, CSEM SA (Switzerland); R. Voelkel, SUSS MicroOptics SA (Switzerland); R. P. Stanley, CSEM SA (Switzerland)
- 8613 1H **Towards high-rate fabrication of photonic devices utilizing a combination of roll-to-roll compatible imprint lithography and ink jet printing methods [8613-53]**
X. Lin, The Univ. of Texas at Austin (United States); T. Ling, Univ. of Michigan (United States); H. Subbaraman, Omega Optics, Inc. (United States); L. J. Guo, Univ. of Michigan (United States); R. T. Chen, The Univ. of Texas at Austin (United States)
- 8613 1I **An improved wire grid polarizer for thermal infrared applications [8613-54]**
M. C. George, J. Bergquist, B. Wang, R. Petrova, H. Li, E. Gardner, Moxtek Inc. (United States)
- 8613 1N **Fabrication of subwavelength holes using nanoimprint lithography [8613-59]**
A. Weiss, J. Besser, M. Baum, R. Saupe, T. Otto, T. Gessner, Fraunhofer-Institut für Elektronische Nanosysteme (Germany)

Author Index

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Mike P. C. Watts, Impattern Solutions (United States)

Session Chairs

- 1 Plasmonic Structures I
Georg von Freymann, Technische Universität Kaiserslautern
(Germany)
- 2 Novel Approaches to Direct Laser Writing
Vygantas Mizeikis, Shizuoka University (Japan)
- 3 Precise Material Deposition
Winston V. Schoenfeld, CREOL, The College of Optics and Photonics,
University of Central Florida (United States)
- 4 3D Structures
Michael Thiel, Nanoscribe GmbH (Germany)
- 5 Plasmonic Structures II
Georg von Freymann, Technische Universität Kaiserslautern
(Germany)
- 6 Large Area Structuring
Georg von Freymann, Technische Universität Kaiserslautern
(Germany)
- 7 Novel Applications and Materials for DLW
Pradeep Srinivasan, Intel Corporation (United States)
- 8 Nano- and Micro-optic Applications
Shanalyn A. Kemme, Sandia National Laboratories (United States)